

L Number	Hits	Search Text	DB	Time stamp
8	0	(ALD or atomic near layer near deposition) and (Aluminum near oxide) and (anneal)and (conformal) and (magnetic near head)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/12/19 10:38
15	0	(ALD or atomic near layer near deposition) and (Aluminum near oxide) and (anneal)and (magnetic near head)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/12/19 10:38
1	24	(ALD or atomic near layer near deposition) and (Aluminum near oxide) and (anneal)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/12/19 10:38